

## TOUCHSCREEN SERIES C FOR 6" WAFERS

# AUTOMEGASAMDRI®-936

*RECIPE CAPABLE WITH PROCESS DATA REVIEW*

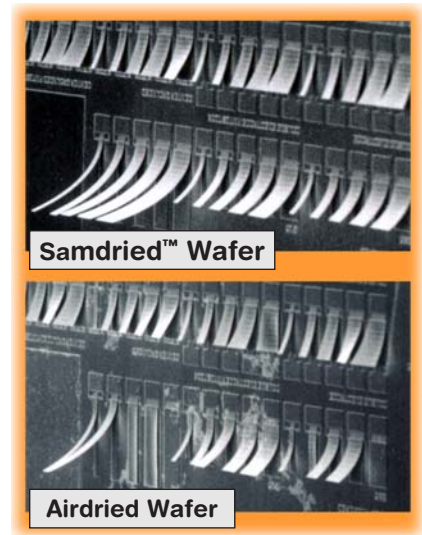
**tousimis**



- The New Supercritical Automegasamdri®-936 System was developed by our in-house design team whose goal was to listen to and incorporate your needs into our next generation.

- The classic features you have come to expect for decades that enable smooth operation, precise control and reproducibility are again evident in our most current design!

- **Process up to Five 6" Wafers per Process Run**
- **Touchscreen Programmable Interface**
- **First Time Ever...Previous Run Data Review**
- **Integrated Chiller Loop Decreases LCO<sub>2</sub> Consumption**
- **Easy Facilitation with Small Foot Print Design**

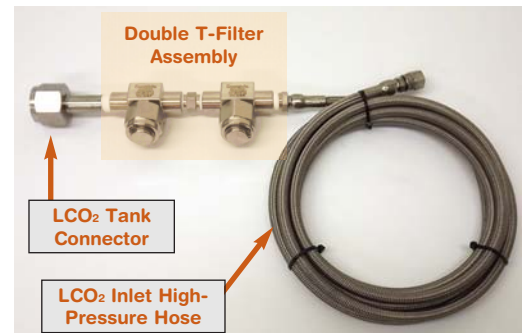


## FEATURES

- A dedicated initial Slow Fill into the process chamber allows ideal fluid dynamics preserving the most sensitive micro devices.
- Maintenance made easy via accessible components including the external Post-Purge-Filter assembly.
- Patent Pending "Vortex Swirl": Non-mechanical stirring chamber allowing for fluid dynamic exchange without the need for particle generating friction causing devices.\*
- Extremely Efficient integrated Closed Cooling Loop dropping chamber temperature quickly for shorter process run times.\*
- The internal SOTER(tm) condenser\* quietly captures and separates CO<sub>2</sub> exhaust and waste alcohols.
- Our original Chamber Inserts enable chamber I.D. variance of chamber I.D. maximizing efficiency in LCO<sub>2</sub> consumption, process time, and providing multiple size wafer process capability!
- Process chamber LCO<sub>2</sub> filtration down to 0.08µm with 99.999%+ particle retention.
- Processes up to five 6" wafers each run. Included are the following HF Compatible Wafer Holders: 6", 4", 3", 2" and 10mm Die Holders.
- Chamber Illumination via viewing window facilitates chamber status visualization.\*
- Automatic process with factory default recipe or the ability to customize your own!\*
- All internal surfaces are inert to CO<sub>2</sub> and ultrapure alcohols.
- Repeatable operating parameters insuring "reproducibility" of results.
- Safety operation features integrated into both temperature and pressure automatic regulation.
- All electronic components meet CE, UL and/or U.S. Military Specifications.
- Clean room static-free compatible design.

## SPECIFICATIONS

- Cabinet: 19.8" (50.3cm) Width x 31.7" (80.6cm) Depth x 44.5" (113.0cm) Height
- System Set-Up Area Footprint: 27" (68.6cm) Width x 38" (96.5cm) Depth
- Chamber size: 6.50" I.D. x 1.25" Depth / Chamber volume: 679 ml
- 120V or 220V / 50-60Hz
- LCO<sub>2</sub> flow is precisely controlled through Micro Metering Valves with Vernier handles for adjustment ease.\*



**Standard Accessories**

## STANDARD ACCESSORIES

- High Pressure LCO<sub>2</sub> flexi-SS316 Braided line for safe operation and easy installation 10ft/3m length included with system. (Other lengths available upon request up to 100 ft /30m)
- Double T-Filter Assembly (#8785) pre-installed onto the chamber LCO<sub>2</sub> supply high-pressure hose.
- Static free exhaust tubing included for all exhaust ports.
- Spare chamber O-rings (3), chamber lamps (2), and slo-blow fuses (2x3A and 2x8A).
- Chamber Inserts included: 6" to 4" / 4" to 3" / 3" to 2" / 2" to 1.25" ! Allows for multiple wafer size drying.
- HF compatible wafer holders included: 6", 4", 3", 2" and 10mm square die. Each holder can load up to five substrates each.
- 2 year warranty on all parts and labor.
- Free lifetime technical support.